

# INTRODUCTION

## SYNERGY SYSTEM DESCRIPTION

The Synergy system is designed to clean wafers using options for a variety of chemical processes which operate in conjunction with the mechanical processes.

The system is composed of seven components which operate together to meet processing requirements.

### INPUT STATION

Initiates the cleaning cycle by transporting the wafers out of the cassette and into Brush Station #1.

### BRUSH STATION #1

Brush Station #1 is the first brush station the wafer enters in the processing cycle. The first scrub process is performed here.

### BRUSH STATION #2

Brush Station #2 is the second brush box the wafer enters in the processing cycle. The second wafer scrub process is performed in this station.

### SPIN STATION

Rinses and dries the wafer after they have completed the cleaning procedure. First, the wafer is rinsed, then the wafer is spun to remove DI water while a heat lamp assists in completing the drying process.

### UNLOAD HANDLER

A mechanical arm which transfers the clean wafer from the spin station to the output station.

### OUTPUT STATION

Contains the cassette into which the clean wafers are placed by the unload handler, after processing.